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Q5  
10 33. (Amended) A scanning exposure method in which a  
11 pattern area of a mask is transferred onto a sensitive plate  
12 through a projection system in a scanning manner, the method  
13 comprising the steps of:

14 (a) irradiating the mask with a radiation in order to  
15 project an image portion of said pattern area of the mask  
16 onto the plate through said projection system;

17 (b) synchronously scanning each of the mask and the  
18 plate relative to said projection system in a scanning  
19 direction at a predetermined velocity ratio by using a  
20 scanning mechanism for the scanning exposure, wherein a  
21 scanning velocity of the mask is different from a scanning  
22 velocity of the plate;

23 (c) detecting a deviation between an ideal positional  
24 relation and an actual positional relation of the mask and  
25 the plate at a term of the scanning exposure; and

26 (d) correcting a position of the mask determined by  
27 said scanning mechanism for decreasing said detected  
28 deviation by using a fine moving mechanism provided on said  
29 scanning mechanism at the term of the scanning exposure.

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1        36. (Amended) A scanning exposure method in which a  
2        pattern of a mask is transferred onto a sensitive plate  
3        through a projection system in a scanning manner, the method  
4        comprising the steps of:

5            (a) irradiating the mask with a radiation in order to  
6        project an image of said pattern of the mask onto the plate  
7        through said projection system;

8            (b) synchronously scanning each of the mask and the  
9        plate relative to said projection system by using a scanning  
10       mechanism for a scanning exposure wherein a scanning  
11       velocity of the mask is different from a scanning velocity  
12       of the plate;

13           (c) detecting a positional deviation between the mask  
14       and the plate at a term of the scanning exposure; and

15           (d) correcting a position of the mask determined by  
16       said scanning mechanism for decreasing said detected  
17       deviation at the term of the scanning exposure.

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1        96. (Amended) A method for manufacturing a circuitry  
2        element with use of the method as defined in claim 68.

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1        128. (Amended) A method for manufacturing a circuitry  
2        element with use of a scanning exposure apparatus made by  
3        using the method as defined in claim 97.

Please add the following claims:

Sub 419  
1        --129. An apparatus according to claim 39, wherein  
2        during movement of said first object by said first driving  
3        system, said second driving system rotates said first object  
4        about a rotation axis passing through a predetermined point  
5        in an illumination region of exposure beam irradiated to  
6        said first object.--

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B 6  
1        --130. An apparatus according to claim 58, wherein  
2        said first measuring device includes a first interferometer  
3        system, and said second measuring device includes a second  
4        interferometer system.--

Sub 415  
1        --131. An apparatus according to claim 130, wherein:  
2        said first interferometer system has a measuring axis  
3        for measuring the position of said first object in said  
4        first direction, a measuring axis for measuring the position  
5        of said first object in a direction which crosses said first  
6        direction and a measuring axis for measuring information on  
7        rotation of said first object, and  
8        said second interferometer system has a measuring axis  
9        for measuring the position of said second object in said  
10       second direction, a measuring axis for measuring the  
11       position of said second object in a direction which crosses  
12       said second direction and a measuring axis for measuring  
13       information on rotation of said second object.--

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1        --137. A method according to claim 87, wherein said  
2        positional information of the first object includes  
3        positional information of said first object in a direction  
4        which crosses said first direction, and  
5        said positional information of the second object  
6        includes positional information of said second object in a  
7        direction which crosses said second direction.--

Cmt  
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1        --138. A method according to claim 87, wherein  
2        said positional information of the first object  
3        includes information on rotation of the first object; and  
4        said positional information of the second object  
5        includes information on rotation of the second object.--

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1        --139. A method according to claim 99, wherein during  
2        movement of said first object by said first driving system,  
3        said second driving system rotates said first object about a  
4        rotation axis passing through a predetermined point in an  
5        illumination region of exposure beam irradiated onto said  
6        first object.--

1        --140. A method according to claim 97, further  
2        comprising:  
3        providing a fourth driving system which moves said  
4        second object in a direction which crosses said second  
5        direction.--